

# (12) International Application Status Report

**Received at International Bureau:** 05 July 2012 (05.07.2012)

**Information valid as of:** 10 December 2012 (10.12.2012)

**Report generated on:** 18 January 2021 (18.01.2021)

**(10) Publication number:**

WO2013/002070

**(43) Publication date:**

03 January 2013 (03.01.2013)

**(26) Publication language:**

Japanese (JA)

**(21) Application Number:**

PCT/JP2012/065643

**(22) Filing Date:**

19 June 2012 (19.06.2012)

**(25) Filing language:**

Japanese (JA)

**(31) Priority number(s):**

2011-142157 (JP)

**(31) Priority date(s):**

27 June 2011 (27.06.2011)

**(31) Priority status:**

Priority document received (in compliance with PCT Rule 17.1)

**(51) International Patent Classification:**

**C08L 77/06** (2006.01); **B32B 27/34** (2006.01); **B65D 65/40** (2006.01); **B65D 81/26** (2006.01); **C08J 5/18** (2006.01)

**(71) Applicant(s):**

MITSUBISHI GAS CHEMICAL COMPANY, INC. [JP/JP]; 5-2, Marunouchi 2-chome, Chiyoda-ku, Tokyo 1008324 (JP) *(for all designated states except US)*

ODA, Takafumi [JP/JP]; c/o Mitsubishi Gas Chemical Company, Inc., Hiratsuka Research Laboratory, 6-2, Higashiyawata 5-chome, Hiratsuka-shi, Kanagawa 2540016 (JP) *(for US only)*

OTAKI, Ryoji [JP/JP]; c/o Mitsubishi Gas Chemical Company, Inc., Hiratsuka Research Laboratory, 6-2, Higashiyawata 5-chome, Hiratsuka-shi, Kanagawa 2540016 (JP) *(for US only)*

ISHII, Kentaro [JP/JP]; c/o Mitsubishi Gas Chemical Company, Inc., Hiratsuka Research Laboratory, 6-2, Higashiyawata 5-chome, Hiratsuka-shi, Kanagawa 2540016 (JP) *(for US only)*

ARAKAWA, Shota [JP/JP]; c/o Mitsubishi Gas Chemical Company, Inc., Hiratsuka Research Laboratory, 6-2, Higashiyawata 5-chome, Hiratsuka-shi, Kanagawa 2540016 (JP) *(for US only)*

**(72) Inventor(s):**

ODA, Takafumi; c/o Mitsubishi Gas Chemical Company, Inc., Hiratsuka Research Laboratory, 6-2, Higashiyawata 5-chome, Hiratsuka-shi, Kanagawa 2540016 (JP)

OTAKI, Ryoji; c/o Mitsubishi Gas Chemical Company, Inc., Hiratsuka Research Laboratory, 6-2, Higashiyawata 5-chome, Hiratsuka-shi, Kanagawa 2540016 (JP)

ISHII, Kentaro; c/o Mitsubishi Gas Chemical Company, Inc., Hiratsuka Research Laboratory, 6-2, Higashiyawata 5-chome, Hiratsuka-shi, Kanagawa 2540016 (JP)

ARAKAWA, Shota; c/o Mitsubishi Gas Chemical Company, Inc., Hiratsuka Research Laboratory, 6-2, Higashiyawata 5-chome, Hiratsuka-shi, Kanagawa 2540016 (JP)

**(74) Agent(s):**

OHTANI, Tamotsu; OHTANI PATENT OFFICE, Bridgestone Toranomon Bldg. 6F., 25-2, Toranomon 3-chome, Minato-ku, Tokyo 1050001 (JP)

**(54) Title (EN):** FILM AND FILM PACKAGING CONTAINER

**(54) Title (FR):** FILM ET CONTENANT D'EMBALLAGE À BASE DU FILM

**(54) Title (JA):** フィルム及びフィルム包装容器

**(57) Abstract:**

**(EN):** A film including a layer formed from a resin composition comprising a polyamide compound (A) and a resin (B), wherein the polyamide compound (A) comprises: 25-50mol% of diamine units, including not less than 50mol% of a specific diamine unit; 25-50mol% of dicarboxylic acid units, including not less than 50mol% of a specific dicarboxylic acid unit; and 0.1-50mol% of a specific constituent unit.

**(FR):** L'invention concerne un film comprenant une couche formée d'une composition de résine comprenant un composé polyamide (A) et une résine (B), le composé polyamide (A) comprenant 25-50 % en moles d'unités diamine, ne comprenant pas

moins de 50 % en moles d'une unité diamine spécifique ; 25-50 % en moles d'unités acide dicarboxylique, ne comprenant pas moins de 50 % en moles d'une unité acide dicarboxylique spécifique ; et 0,1-50 % en moles d'une unité constitutive spécifique.

(JA): ポリアミド化合物(A)及び樹脂(B)を含有する樹脂組成物から形成される層を含むフィルムであって、該ポリアミド化合物(A)が、特定のジアミン単位を50モル%以上含むジアミン単位25～50モル%と、特定のジカルボン酸単位を50モル%以上含むジカルボン酸単位25～50モル%と、特定の構成単位0.1～50モル%とを含有する、フィルム。

### International search report:

Received at International Bureau: 20 September 2012 (20.09.2012) [JP]

### International Report on Patentability (IPRP) Chapter II of the PCT:

Not available

### (81) Designated States:

AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, QA, RO, RS, RU, RW, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW

European Patent Office (EPO) : AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR

African Intellectual Property Organization (OAPI) : BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

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Eurasian Patent Organization (EAPO) : AM, AZ, BY, KG, KZ, RU, TJ, TM